On the Significance of Metastable States in Low Pressure Capacitively Coupled Oxygen Discharge

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Introduction

- Oxygen is a weakly electronegative gas and the presence of negative ions has a strong influence on the kinetics and dynamics of the oxygen discharge.
- The oxygen discharge is of vital importance in various materials processing applications such as:
  - ashing of photoresist
  - etching of polymer films
  - oxidation and deposition of thin film oxides
- The oxygen chemistry is rather involved, in particular due to the presence of metastable molecular and atomic oxygen and their role in dissociative attachment and detachment processes.
Outline

■ The 1D particle-in-cell/Monte Carlo collision simulation
■ The oxygen discharge
■ Capacitively Coupled Oxygen Discharge at 13.56 MHz
  ■ Pressure dependence – including $O_2(a^1\Delta_g)$
  ■ Including both $O_2(a^1\Delta_g)$ and $O_2(b^1\Sigma_g)$
  ■ Including secondary electron emission
■ Summary
The 1D particle-in-cell/Monte Carlo collision simulation
The oopd1 1d-3v PIC/MCC code

- We use the oopd1 (objective oriented plasma device for one dimension) code to simulate the discharge
- The oopd1 code was originally developed at the Plasma Theory and Simulation Group at UC Berkeley
- It has 1 dimension in space and 3 velocity components for particles (1d-3v)
- The oopd1 code is supposed to replace the widely used xpdx1 series (xpdp1, xpdcl and xpds1)
- It is developed to simulate various types of plasmas, including processing discharges, accelerators and beams
  - Modular structure
  - Includes relativistic kinematics
  - Particles can have different weights

The oxygen discharge
The oxygen discharge

- We consider a discharge that consists of:
  - electrons
  - the ground state oxygen molecule \( \text{O}_2(X^3\Sigma^-) \)
  - the metastable oxygen molecule \( \text{O}_2(a^1\Delta_g) \)
  - the metastable oxygen molecule \( \text{O}_2(b^1\Sigma_g) \)
  - the ground state oxygen atom \( \text{O}(^3\text{P}) \)
  - the metastable oxygen atom \( \text{O}(^1\text{D}) \)
  - the negative oxygen ion \( \text{O}^- \)
  - the positive oxygen ions \( \text{O}^+ \) and \( \text{O}_2^+ \)

- We apply a global model\(^1\) beforehand to calculate the partial pressure of the various neutrals

The oxygen discharge

The reaction set for the oxygen is comprehensive and for this study includes 67 reactions

B. 1. 1. Capacitively Coupled Oxygen Discharge at 13.56 MHz – pressure dependence – including $\text{O}_2(a^1\Delta_g)$
Capacitively Coupled Oxygen Discharge at 13.56 MHz

- We apply a voltage source with a single frequency
  \[ V(t) = V_{\text{rf}} \sin(2\pi ft) \]

- The electrodes are circular with a diameter of 14.36 cm
- The gap between the electrodes is 4.5 cm
- We set \( V_{\text{rf}} = 222 \text{ V} \) and \( f = 13.56 \text{ MHz} \)
- The neutrals (\( \text{O}_2 \) and \( \text{O} \)) are treated as background gas at \( T_g = 300 \text{ K} \) with a Maxwellian distribution
- The dissociation fraction and the metastable fraction is found using a global model
- The pressure is varied from 10 – 500 mTorr
For a parallel plate capacitively coupled oxygen discharge at 50 mTorr with a gap separation of 4.5 cm by a 222 V voltage source at 13.56 MHz

- $O_2^+$-ion density profile
- $O^+$-ion density profile
- $O^-$-ion density profile
- electron density profile

Gudmundsson and Ventéjou (2015) JAP 118 153302
The sheath width decreases as the pressure is decreased in the pressure range from 50 mTorr to 10 mTorr.

- The sheath widths are largest at 50 mTorr.
- As the pressure is increased from 50 mTorr up to 500 mTorr the sheath width decreases.
- This agrees with what has been observed experimentally in the pressure range 40 – 375 mTorr.

Mutsukura et al. (1990) JAP 68 2657 and van Roosmalen et al. (1985) JAP 58 653
The electron heating profile $J_e \cdot E$

In the pressure range 50 - 500 mTorr the electron heating occurs almost solely in the sheath region.

As the pressure is decreased, the Ohmic heating contribution in the plasma bulk increases and sheath heating decreases.

Gudmundsson and Ventéjou (2015) JAP 118 153302
At low pressure the EEPF is convex, the population of low energy electrons is relatively low.

As the pressure is increased, the number of low energy electrons increases and the number of higher energy electrons (> 10 eV) decreases.

Thus the EEPF develops a concave shape or becomes bi-Maxwellian as the pressure is increased.

Gudmundsson and Ventéjou (2015) JAP 118 153302
Our results agree with the measurements of Lee et al. (2010) which explored experimentally the evolution of the EEPF with pressure in a capacitively coupled oxygen discharge in the pressure range 3 – 100 mTorr.

They find that the EEPF became more distinctly bi-Maxwellian and the density of low energy electrons increases as the gas pressure is increased.
The effective electron temperature drops as the pressure is increased.

When the metastable singlet oxygen molecule $O_2(a^1\Delta_g)$ is added to the discharge model, the effective electron temperature drops, in particular in the electronegative core due to detachment by the metastable $O_2(a^1\Delta_g)$ molecule.

$$O^- + O_2(a^1\Delta_g) \rightarrow \text{products}$$
B. 1. 2. Capacitively Coupled Oxygen Discharge at 13.56 MHz – pressure dependence – including $O_2(a^1\Delta_g)$, $O_2(b^1\Sigma_g)$ and $\gamma_{\text{see}}(E)$
 Capacitively Coupled Oxygen Discharge at 13.56 MHz

- It has been known for decades that the metastable oxygen molecule $O_2(b^1\Sigma_g)$ plays an important role in the oxygen discharge

- Recent global model study indicates there is a significant density of $O_2(b^1\Sigma_g)$ in the oxygen discharge

- The $O_2(b^1\Sigma_g)$ is mainly created through

\[ O_2(X^3\Sigma_g^-)+O(^1D) \rightarrow O_2(b^1\Sigma_g)+O(^3P) \]

The density profiles of charged particles and fast neutrals comparing including $\gamma_{\text{see}}(E)$ and $O_2(a^1\Delta_g)$ (left) and $\gamma_{\text{see}}(E)$, $O_2(a^1\Delta_g)$ and $O_2(b^1\Sigma_g)$ (right) at 50 mTorr.
The spatio-temporal electron heating at 10 mTorr (left) and 50 mTorr (right)

The four cases explored are:

- (a) detachment neither by $O_2(a^1\Delta_g)$ nor $O_2(b^1\Sigma^+_g)$
- (b) only detachment by $O_2(b^1\Sigma^+_g)$ included
- (c) only detachment by $O_2(a^1\Delta_g)$ included
- (d) both detachment by $O_2(a^1\Delta_g)$ and $O_2(b^1\Sigma^+_g)$ included
Capacitively Coupled Oxygen Discharge at 13.56 MHz

- The number of cold electrons increases as $O_2(b^1\Sigma_g)$ is added to the discharge model.
- The electron heating in the bulk drops to zero.
- The effective electron temperature profile changes significantly when detachment by singlet metastables is added to the reaction set.
- 10 mTorr, 50 mTorr and 200 mTorr

Gudmundsson and Hannesdottir, AIP Conf. Proc. accepted 2016
Capacitively Coupled Oxygen Discharge at 13.56 or 27.12 MHz

- The spatio-temporal electron heating at 10 mTorr with a gap separation of 4.5 cm driven by a 222 V voltage source at 13.56 MHz (left) and 27.12 MHz (right)
Capacitively Coupled Oxygen Discharge Dual Frequency at 13.56 MHz + 27.12 MHz

- The ion energy distribution (IED)
- A dual frequency (13.56 MHz + 27.12 MHz) parallel plate capacitively coupled oxygen discharge at 75 mTorr
  - (a) Detachment by $\text{O}_2(a^1\Delta_g)$ and $\text{O}_2(b^1\Sigma_g)$ included
  - (b) Detachment by $\text{O}_2(a^1\Delta_g)$ and $\text{O}_2(b^1\Sigma_g)$ excluded
- For a larger discharge gap ($L = 6.5$ cm), the peak in the IED is much more apparent in the case where the full reaction set is used in the discharge model

Hannesdottir and Gudmundsson, (2016) to be submitted
Capacitively Coupled Oxygen Discharge at 13.56 MHz

- Comparison to experimental findings:
  
  \( \gamma_{\text{see}} = 0.0, \)  
  \( 4.4 \% \text{O}_2(a^1\Delta_g) \)

  \( \gamma_{\text{see}} = 0.0, \)  
  \( 4.4 \% \text{O}_2(a^1\Delta_g) \) and \( 4.4 \% \text{O}_2(b^1\Sigma_g) \)

  \( \times \gamma_{\text{see}} = \gamma_{\text{see}}(E), \)  
  \( 4.4 \% \text{O}_2(a^1\Delta_g) \) and \( 4.4 \% \text{O}_2(b^1\Sigma_g) \)

- Experimental findings by Kechkar

(S. Kechkar, Ph.D. Thesis, Dublin City University, January 2015)

Hannesdottir and Gudmundsson (2016) PSST 25 055002
Summary

- We demonstrated particle-in-cell/Monte Carlo collision simulation of a capacitively coupled discharge.
- In an oxygen discharge at low pressure the EEPF is convex and develops a concave shape or becomes bi-Maxwellian as the pressure is increased.
- These results contradict what is commonly found for the capacitively coupled argon discharge where the EEPF evolves from being concave at low pressure to being convex at high pressure.
- Including the detachment processes by the singlet metastable states has a strong influence on the effective electron temperature and electronegativity in the oxygen discharge.
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The slides can be downloaded at http://langmuir.raunvis.hi.is/~tumi/ranns.html

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